Date	User	Film	Recipe	Substrate T	Thickness	Dep.time	JAW EC-400 (Woolam Spec. Ell.)		Dep.rate	Stress	HF e.r. wafer	LPD (light point defects)		AVG dep.rate	AVG+10%	AVG-10%	AVG index@	AVG+1%	AVG -1%	AVG.Stress	Avg+20%	Avg-20%	Additional Notes	Brian Lingg, PM
1/1/2012	User	SiO2	SiO2_10	250° C	(Å)	sec	Index @ 632.8nm	Index @ 1550nm	(nm/min)	(MPa)	(nm/min)	before dep.	after dep.										Deposition done on 4"Si wafer	update this (logbook)
01/06/14	Biljana	SiO2	SiO2_10	250	1013.74	176.6	1.463	1.459	34.44	-401.73		284	1059	35.44	38.98	31.90	1.457	1.472	1.442	-377.30	-452.76	-301.84	Grouped particles	
01/23/14	Biljana	SiO2	SiO2_10	250	1069.74	176.6	1.456	1.445	36.34	-375.92	604.28	159	290	35.44	38.98	31.90	1.457	1.472	1.442	-377.30	-452.76	-301.84	Nice film, not many particles	1/23/14
02/03/14	Biljana	SiO2	SiO2_10	250	1047.82	176.6	1.456	1.451	35.60	-346.54	604.71	304	451	35.44	38.98	31.90	1.457	1.472	1.442	-377.30	-452.76	-301.84	Film is much darker in the center	
02/18/14	Biljana	SiO2	SiO2_10	250	1031.00	176.6	1.454	1.444	35.03	-397.61	545.75	48	274	35.44	38.98	31.90	1.457	1.472	1.442	-377.30	-452.76	-301.84	Film darker in the center	2/14/14 Silane change
03/14/14	Biljana	SiO2	SiO2_10	250	1053.21	176.6	1.455	1.444	35.78	-364.72	600.97	112	222	35.44	38.98	31.90	1.457	1.472	1.442	-377.30	-452.76	-301.84	Film darker in the center	

Avg.Thickness	1043.102
Avg Index	1.457
Index+1%	1.472
Index-1%	1.442
Avg Dep.Rate	35.44
Avg +10%	38.98
Avg - 10%	31.90
Avg. Stress	-377.30
Avg +20%	-452.76
Avg - 20%	-301.84
Avg. HF e.r.	588.928